



<b>Form 1449 (Modified)</b> <b>Information Disclosure Statement By Applicant</b> (Use Several Sheets if Necessary)	Atty Docket No. NOVLP075/NVLS-000820 Applicant: Tipton et al. Filing Date September 26, 2003	Application No.: 10/672,311 Group 2823
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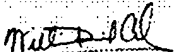
**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication		
WC	C1	Cho et al., "Method for Porogen Removal and Mechanical Strength Enhancement of Low-K Carbon Doped Silicon Oxide Using Low Thermal Budget Microwave Curing", U.S. Application No. 11/280,113, filed November 15, 2005 (Atty Dkt: NOVLP145/NVLS-3106)		
Examiner	<div><div></div><div><small>Digitally signed by W. David Coleman DN: cn=W. David Coleman, o=US, ou=USPTO, ou=2823, email=W.David.Coleman@uspto.gov Reason: I have reviewed this document Date: 2006.05.11 10:44:05 -0400</small></div></div>		Date Considered	05/11/2006

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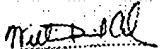
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WC	A1	5,849,640	12.1998	Hsia et al.			
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#### Other Documents

Other Documents				
Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication		
WC	C1	U.S. Office Action mailed December 20, 2005, from U.S Application No. 10/849,568 [Atty Dkt No. NOVLP083/NVLS-2867].		
WC	C2	U.S. Office Action mailed January 9, 2006, from U.S Application No. 10/785,235 [Atty Dkt No. NOVLP085/NVLS-2875].		
WC	C3	U.S. Office Action mailed December 27, 2005, from U.S Application No. 10/789,103 [Atty Dkt No. NOVLP094/NVLS-002919].		
WC	C4	U.S. Office Action mailed December 23, 2005, from U.S Application No. 10/800,409 [Atty Dkt No. NOVLP098/NVLS-002907].		
WC	C5	U.S. Office Action mailed February 7, 2006, from U.S Application No. 10/672,305 [Atty Dkt No. NOVLP069/NVLS-000821].		
WC	C6	Subramonium et al., "Pulsed PECVD Method for Modulating Hydrogen Content in Hard Mask", U.S. Application No. 11/318,269, filed December 23, 2005 (Atty Dkt: NOVLP144/NVLS-3102)		
Examiner	<div><div></div><div><small>Digitally signed by W. David Coleman DN: cn=W. David Coleman, email=william.Coleman@uspto.gov Reason: I have reviewed this document Date: 2006.06.11 10:45:24 -04'00'</small></div></div>		Date Considered	05/11/2006

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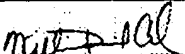
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Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
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WC	A3	2003/0198895 A1	10.2003	Toma et al.			
WC	A4	6,846,380 B2	01.2005	Dickinson et al.			

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#### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
WC	C1	U.S. Office Action mailed February 28, 2006, from U.S Application No. 10/404,693 [Atty Dkt No. NOVLP064/NVLS-794].
WC	C2	U.S. Office Action mailed March 29, 2006, from U.S Application No. 10/800,377 [Atty Dkt No. NOVLP089/NVLS-002886].
Examiner	 <small>Digitally signed by W. David Coleman DN: cn=W. David Coleman, o=US, ou=USPTO, ou=2823, email=William.Coleman@uspto.gov Reason: I have reviewed this document Date: 2006.05.11 10:47:59 -0400</small>	
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